



Thermal Conductance of a Single-Electron Transistor

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Wiedemann-Franz Law

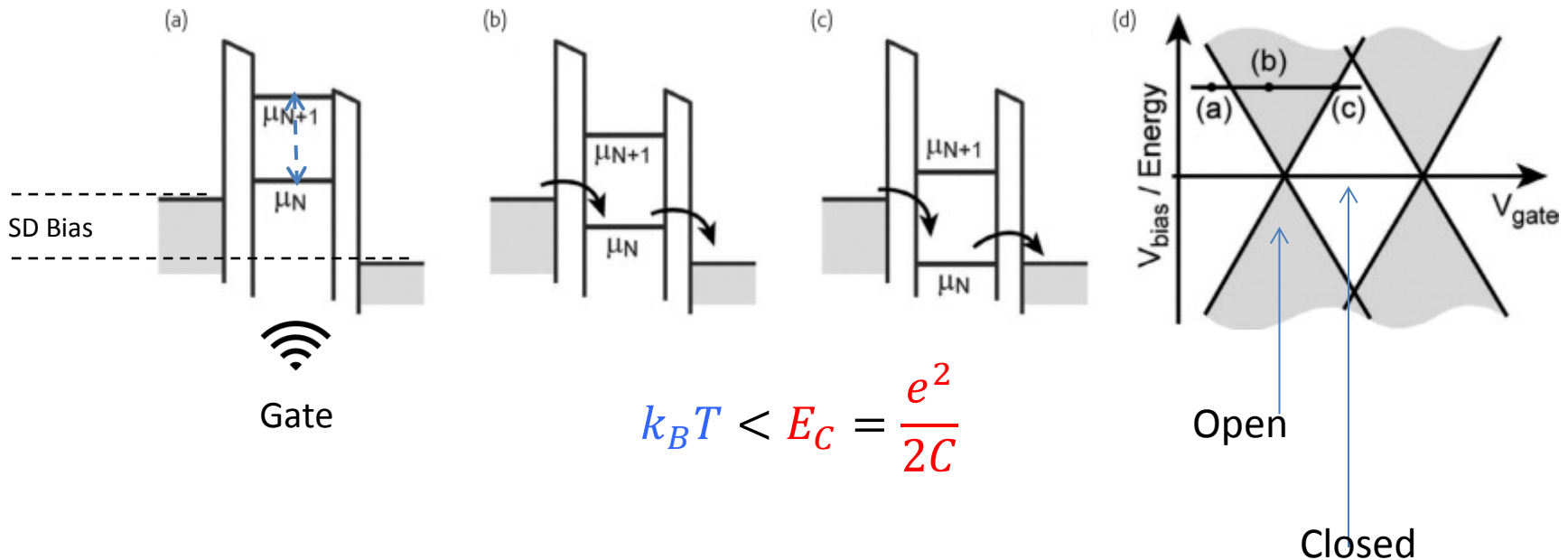
$$\frac{\kappa}{\sigma} = L_0 T$$

$$L_0 = \frac{\pi^2 k_b^2}{3e^2} = 2.44 \times 10^{-18} \text{W}\Omega\text{K}^{-2}$$

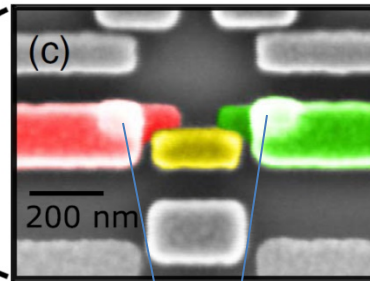
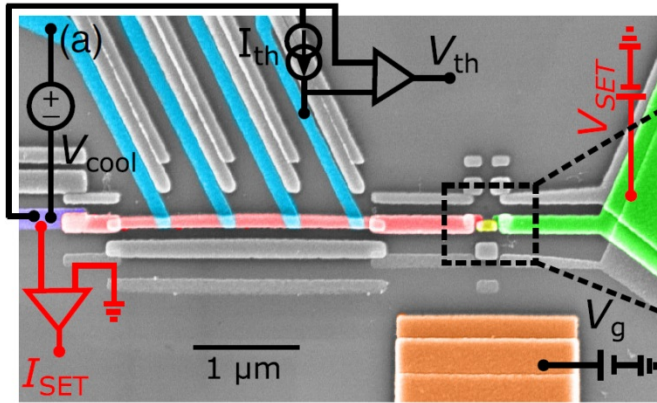
Validity: limiting process

- High temperatures : Phonon scattering
- Deviations----
- Low temperatures : Impurity scattering

Single Electron Transistor



SET Device with NIS Thermometry

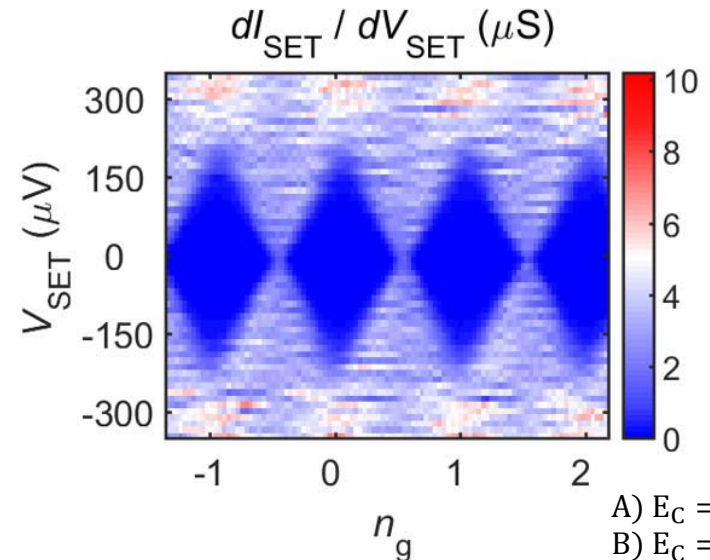
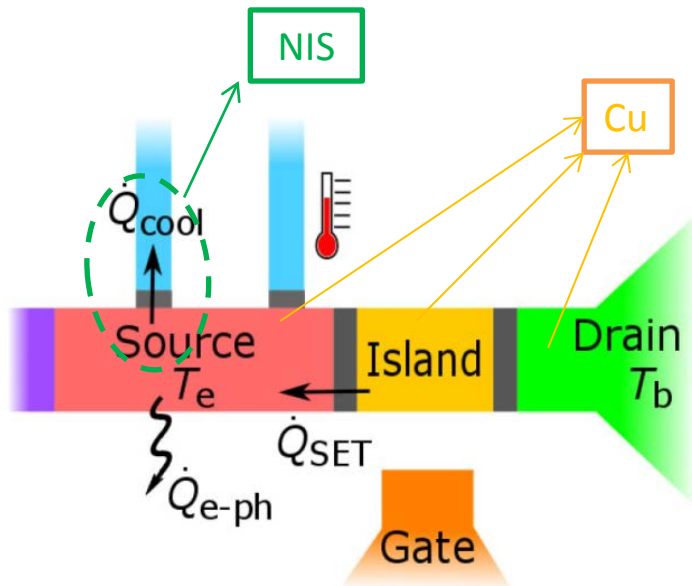


Large ground plane : Au(30nm)

- 1) Cu 30nm for A (164 kΩ)
45nm for B (52 kΩ)
- 2) Al 20nm
in-situ oxidation
- 3) Cu 30nm

Red = charge transport
Black = heat transport

Inverse Proximity Effect*

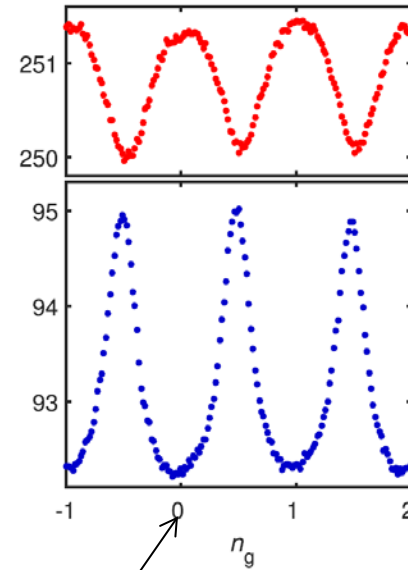
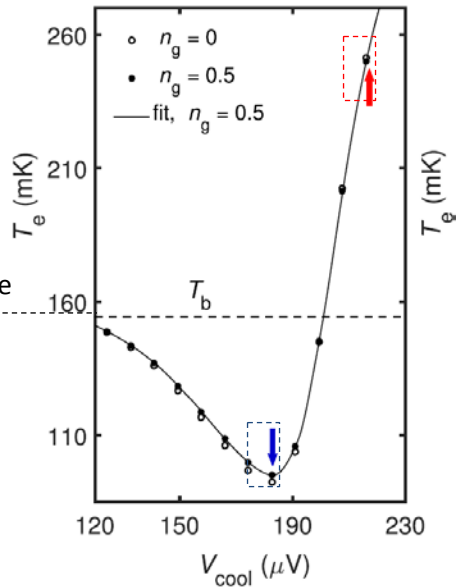


* Koski J.V., et al., Laterally proximized aluminum tunnel junctions, Appl. Phys. Lett. 98, 206501 (2011)

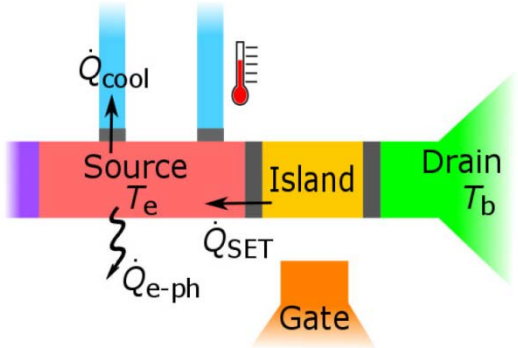
T_e vs T_b : Overheating and Cooling

$T_e > T_b$

$T_e < T_b$

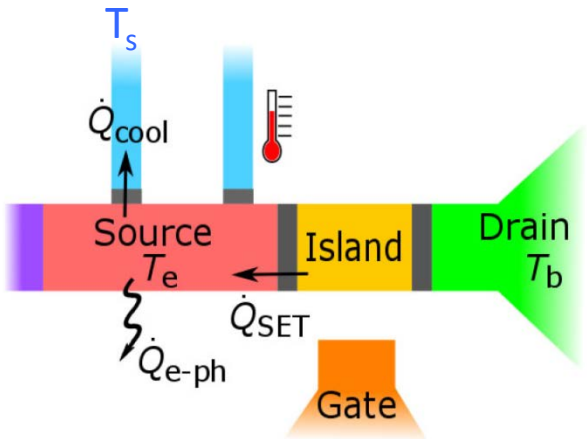


Gate closed



Maximum cooling $\approx \Delta_{Al} = 208 \mu eV$

Analysis



Thermal Balance in the source

$$\dot{Q}_{cool} = \left(\frac{1}{e^2 R_{cool}} \right) \int_{-\infty}^{+\infty} (E - eV_{cool}) \underbrace{n_s(E)}_{\text{BCS DOS}} \underbrace{[f_{source}(E - eV_{cool}) - f_s(E)]}_{\text{Thermal Energy Distribution}} dE - \underbrace{\dot{Q}_0}_{\text{Parasitic Power}}$$

Tunnel
Junction
Resistance

BCS
DOS

Thermal
Energy
Distribution

Parasitic
Power

0.1 fW

Relaxation channel

$$\dot{Q}_{e-ph} = \Sigma v (T_e^5 - T_{ph}^5)$$

$$T_b = T_{ph}$$

$$\dot{Q}_{SET} = \dot{Q}_{cool} + \dot{Q}_{e-ph}$$

dI/dV

Extracted + T_e by NIS + $V_{cool} = T_s(V_{cool})$

Gate open position

$$\frac{\kappa}{\sigma} = L_0 T$$

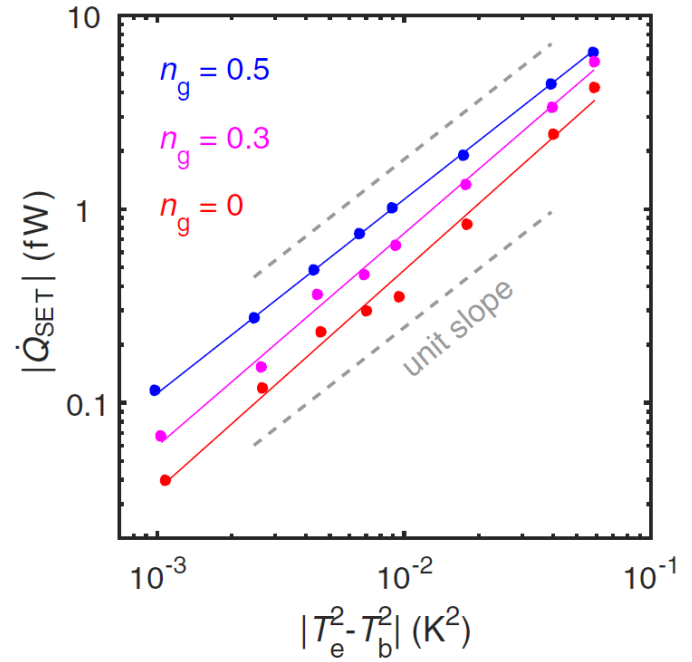
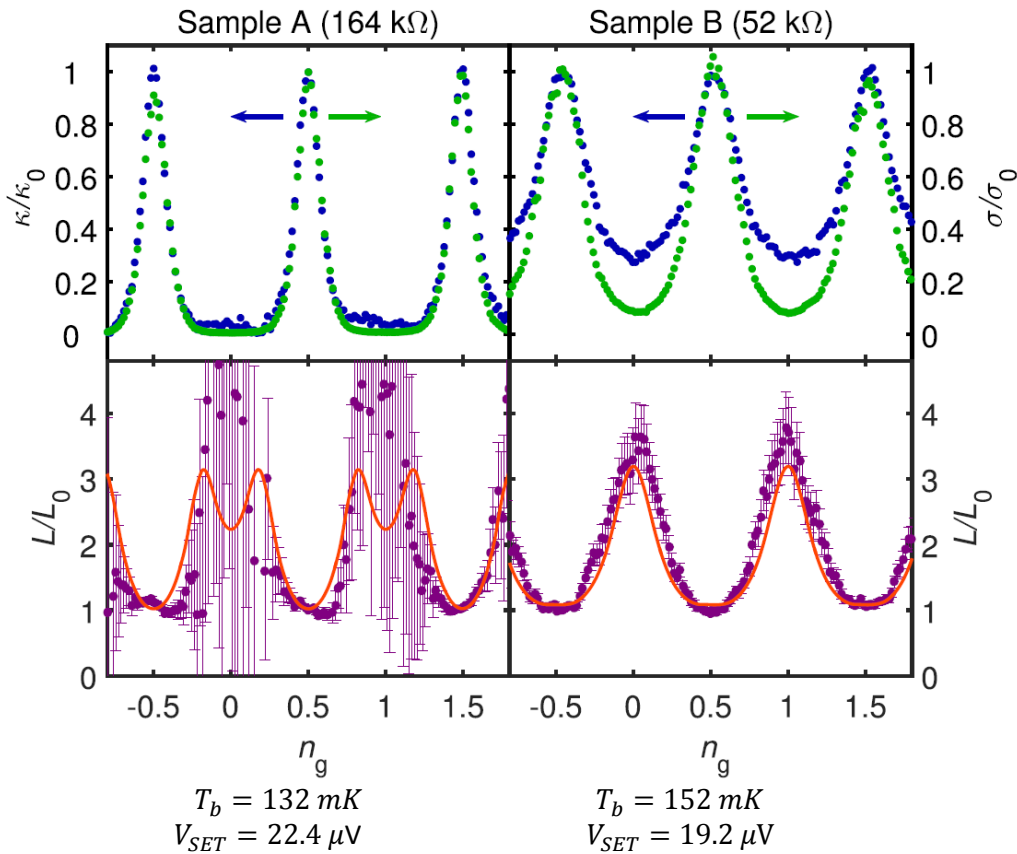
Mesaured $T_e(n_g)$

$$P = \sigma_0 L T_m (T_b - T_e)$$

$$T_m = (T_e + T_b)/2$$

$$\kappa = \frac{\dot{Q}_{SET}}{(T_b - T_e)}$$

Violation of Wiedemann-Franz Law



Large temperature differences

$$\kappa \sim T$$

$$\kappa_0 = \sigma_0 L_0 T_m (n_g = 0.5)$$

$$L = \kappa / (\sigma T_m)$$

$$\frac{L}{L_0} \neq 1$$

$$T_m = (T_e + T_b) / 2$$

Conclusion

Thermal conductance of SET is investigated

Validity of Wiedemann-Franz Law is tested

NIS Thermometry is used

Thermal conductance depends on the SET state

Violations of Wiedemann-Franz Law

Thank you